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## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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John F. ARACKAPARAMBIL et al.

OCT 1 3 2004

Serial No. 10/084,092

Group Art Unit: 2121

Technology Center 2100

Filed: February 28, 2002

Examiner:

For:

COMPUTER INTEGRATED MANUFACTURING TECHNIQUES

## SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Honorable Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

In accordance with the provisions of 37 C.F.R. 1.56, 1.97 and 1.98, the attention of the Patent and Trademark Office is hereby directed to the documents listed on the attached form PTO-1449. It is respectfully requested that the documents be expressly considered during the prosecution of this application, and that the documents be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This Information Disclosure Statement is being filed within three months of the U.S. filing date OR before the mailing date of a first Office Action on the merits. No certification or fee is required.

This submission does not constitute a representation that a search has been made or that no better art exists and does not constitute an admission or representation that any of the listed documents is material or constitutes prior art. If it should be determined that any of the listed documents does not constitute prior art under the United States law, Applicants reserve the right

## Serial No. 10/084,092

to present to the Office the relevant facts and law regarding the appropriate status of such document.

No certification or fee is believed to be required. However, the Commissioner is hereby authorized to charge any additional fees should any be required for this submission, or credit any overpayment to deposit account no. 08-0219.

Respectfully submitted,

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Date: 10/8/04

INFORMATION DISCLOSURE  CITATION IN AN  PE CAPPLICATION  OUT O 8 2004  EXECUTE TRADELLES  U.S. PATENT DO				APPLICANT John F. ARACKAPARAMB FILING DATE February 28, 2002		SERIAL NO. 10/084,092  RECEIVED  OCT 1 3 2004  echnology Center 2100  BIL et al.  GROUP 2121	
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EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

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